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☐ 1. Document ID: DE 4228344 A1

L7: Entry 1 of 2

File: EPAB

Mar 10, 1994

PUB-NO: DE004228344A1

DOCUMENT-IDENTIFIER: DE 4228344 A1

TITLE: Photoresist deposition for micro-structuring process - using combination of electro-hydrodynamic ion source and ion spray deposition

PUBN-DATE: March 10, 1994

INVENTOR-INFORMATION:

NAME

FELD, HERBERT DR

SUNDERMEIER, CHRISTIAN DIPL ING

KNOLL, MEINHARD PROF DR

COUNTRY

DE

DE

DE

ASSIGNEE-INFORMATION:

NAME

INST CHEMO U BIOSENSORIK E V

COUNTRY

DE

APPL-NO: DE04228344

APPL-DATE: August 26, 1992

PRIORITY-DATA: DE04228344A (August 26, 1992)

US-CL-CURRENT: 430/935

INT-CL (IPC): G03F 7/16; B05B 5/00; B05B 5/03; B05D 1/02

EUR-CL (EPC): B05D001/00; B05D001/04, G03F007/16 , B05B005/03

ABSTRACT:

CHG DATE=19990617 STATUS=O>A process for photoresist coating of micro-mechanical three-dimensionally structure components comprises (i) producing charged mesoscopic photo-resist droplets of 0.05-1 micron diameter by means of an electrohydrodynamic ion source; and (ii) spraying the droplets onto the substrate by combination with the ion spray method. Appts. for carrying out the above process is also claimed. ADVANTAGE - Homogenous photoresist layers with variable thickness (typically max. 1 micron) are produced by an inexpensive process.

Full	Title	Citation	Front	Review	Classification	Date	Reference	Sequences	Attachments
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☐ 2. Document ID: DE 4228344 A1 DE 4228344 C2

L7: Entry 2 of 2

File: DWPI

Mar 10, 1994

DERWENT-ACC-NO: 1994-084156

DERWENT-WEEK: 199927

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TITLE: Photoresist deposition for micro-structuring process - using combination of electro-hydrodynamic ion source and ion spray deposition

INVENTOR: FELD, H; KNOLL, M ; SUNDERMEIER, C

PATENT-ASSIGNEE:

ASSIGNEE

CODE

INST CHEMO & BIOSENSORIK EV

CHEMN

PRIORITY-DATA: 1992DE-4228344 (August 26, 1992)

PATENT-FAMILY:

PUB-NO	PUB-DATE	LANGUAGE	PAGES	MAIN-IPC
<u>DE 4228344 A1</u>	March 10, 1994		005	G03F007/16
<u>DE 4228344 C2</u>	June 10, 1999		000	G03F007/16

APPLICATION-DATA:

PUB-NO	APPL-DATE	APPL-NO	DESCRIPTOR
DE 4228344A1	August 26, 1992	1992DE-4228344	
DE 4228344C2	August 26, 1992	1992DE-4228344	

INT-CL (IPC): B05B 5/00; B05B 5/025; B05B 5/03; B05B 5/035; B05D 1/02; B05D 1/04; G03F 7/16

ABSTRACTED-PUB-NO: DE 4228344A

BASIC-ABSTRACT:

A process for photoresist coating of micro-mechanical three-dimensionally structure components comprises (i) producing charged mesoscopic photo-resist droplets of 0.05-1 micron diameter by means of an electrohydrodynamic ion source; and (ii) spraying the droplets onto the substrate by combination with the ion spray method.

Appts. for carrying out the above process is also claimed.

ADVANTAGE - Homogenous photoresist layers with variable thickness (typically max. 1 micron) are produced by an inexpensive process.

CHOSEN-DRAWING: Dwg.1/1

TITLE-TERMS: PHOTORESIST DEPOSIT MICRO STRUCTURE PROCESS COMBINATION ELECTRO HYDRODYNAMIC ION SOURCE ION SPRAY DEPOSIT

DERWENT-CLASS: A89 G06 L03 P42 P84 X25

CPI-CODES: A11-B05A; A11-B05B1; A12-L02; G06-D04; G06-E04; L04-C06B;

EPI-CODES: X25-K01;

UNLINKED-DERWENT-REGISTRY-NUMBERS: 0270U; 0272U

POLYMER-MULTIPUNCH-CODES-AND-KEY-SERIALS:

Key Serials: 0036 0223 0229 2318 2378 2419 2507 2654

Multipunch Codes: 017 03- 316 332 371 398 427 431 575 596 681 726

SECONDARY-ACC-NO:

CPI Secondary Accession Numbers: C1994-038667

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